

Stress Estimation of a Drain Current in Sub-threshold regime of amorphous Si:H

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Abstract

We have investigated the threshold voltage shifts (ΔV_{th}) and drain current level shift (ΔI_{ds}) in sub-threshold region of a-Si:H TFTs induced by DC Bias (V_{gs} and V_{ds}) - Temperature stress (BTS) condition. We plotted the transfer curves and the ΔV_{th} contour maps as V_{ds} - V_{ds} stress bias and Temperature to examine the severe damage cases on TFTs. Also, by drawing out the time-dependent transfer curve (I_{ds} - V_{gs}) in the region of $10^{-8} \sim 10^{-13}$ (A) current level, we can estimate the failure time of TFTs in a operating condition.

1. Introduction

In the LCD and AMOLED display based on a-Si:H TFT, there have been a lot of concerns for the reliability of image quality and life time of display. As increasing the using time, the electrical properties of display is degraded because of electrical instability of a-Si:H TFT. This electrical instability has explained with two mechanisms [1-4]. One is the charge trapping in the gate insulator, which makes the transfer characteristics parallel shifted. And the other mechanism is state defect creation at/ or near the a-Si:H / gate insulator interface, which makes the sub-threshold slope (S-factor) increase and degenerates the switching ability of TFTs. The instability of TFTs in BTS is mixed with above two mechanisms and depends on the manufacturing process and environment [5].

This electrical instability of TFTs caused a lot of reliability issues on the image quality. Though initial LCD products have no fault, after several years they starts to be revealed the faults such as mura, vertical cross-talk, etc. Especially, the vertical cross-talk is one of the most frequently revealed faulty, which are caused by off-state I_{ds} current level in sub-threshold region. Therefore, in this paper, we focused the ΔI_{ds}

current level as well as ΔV_{th} shift varied with stress time.

2. Experimental

We have examined the electrical instability with the inverted staggered bottom-gate a-Si:H TFTs. We used the individual TFT for a BTS condition. All TFTs in this paper have about 4000 Å thick a-SiNx:H as a gate insulator layer, 2000 Å thick a-Si:H as a active layer and 500 Å thick n^+ layer between Drain/Source electrode and a-Si:H layer. Also, TFT size, W/L is = 24 / 5 μm . And these TFTs were manufactured by the same design and process. Measurement procedures are (1) measuring the pre-stressed transfer characteristic, (2) applying stress as a function of stress time in the given BTS condition and (3) measuring post-stressed transfer characteristic, afterward repeating (2) and (3) for the time-dependent BTS condition. The HP4156C semiconductor Analyzer is used for the measurement and bias stress.

3. Results and discussion

In the light of LCD operation, the TFT is always stressed by varing V_{gs} and V_{ds} during holding time region. Because all V_{gs} and V_{ds} bias condition affects to the TFT instability [9], we first examined the ΔV_{th} shift as functions of the stress V_{gs} and V_{ds} bias at the constant stress time (1000sec). Figure 1 and 2 show the transfer characteristics and contour plots of ΔV_{th} , respectively. In figure 2, V_{th} was mainly shifted by V_{gs} stress not V_{ds} , because the contour lines vary along the V_{gs} bias axis (x-axis). It indicates that main cause electrical instability of the TFT is the V_{gs} bias. So, we have focused the stress V_{gs} bias and among the rest, the negative bias. Because all gate biases remain in the negative bias during the holding time

region. Moreover the holding time region is much longer than the charging time region (V_{gs} is positive). For example, in case of the UXGA LCD panel, the ratio holding time and charging time is 16654us / 12.5us (1332 times).

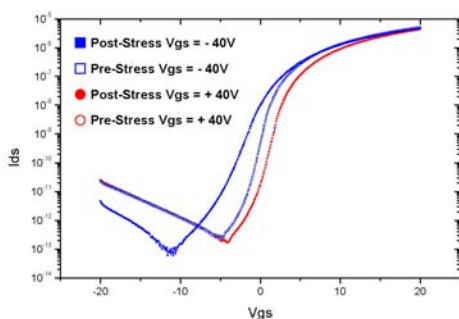
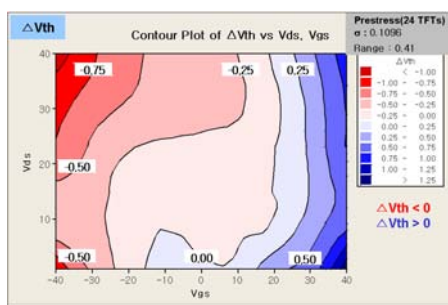
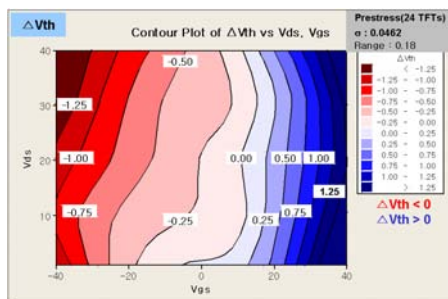


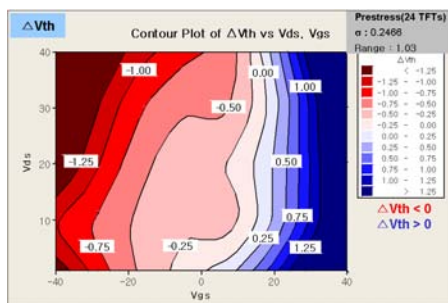
Figure 1. The pre-stressed (open symbols) and post-stressed (solid symbols) transfer curves. BTS conditions are stress $V_{ds} = 10V$, stress time = 1000 sec and temperature = $60^\circ C$.



a) Room Temperature



b) $60^\circ C$



c) $80^\circ C$

Figure 2. The contour plots of ΔV_{th} as a function of stress V_{gs} and V_{ds} in (a) Room Temperature, (b) $60^\circ C$ and (c) $80^\circ C$. Stress time is fixed in 1000 sec. Their standard deviations and ranges on the V_{th} of pre-stressed TFT are demonstrated in the plot boxes.

Also, figure 1 shows the pre-stressed and post-stressed transfer curves (measurement $V_{ds} = 15V$) of TFTs. In the positive V_{gs} stress condition, the transfer curve shifted the parallel positive direction and in the negative, transfer characteristics shifted the negative direction and degraded the sub-threshold slope (S-factor). In respect of leakage current during holding time region, the negative V_{gs} is more severe stress than the positive.

For estimation on the reliability of display quality, we have monitored the ΔV_{th} as a function of stress time. Also, we have defined the V_{min} as the voltage at the minimum I_{ds} in electron conduction region to estimate the I_{ds} level in sub-threshold regime. Figure 3 (a) shows ΔV_{th} and (b) ΔV_{min} as a function of stress time. About ΔV_{th} , previous reports [1, 6-8] well described it as the form of a stretched exponential function.

$$\Delta V_{th}(t_{stress}) = \Delta V_{th_0} \cdot \left\{ 1 - \exp \left[- \left(\frac{t_{stress}}{\tau} \right)^\beta \right] \right\} \quad (1)$$

With

$$\Delta V_{th_0} = \Delta V_{th}(\infty) = V_{gs}^{stress} - V_{th}(0) \quad (2)$$

where ΔV_{th_0} is the shift at infinite time, τ is a characteristics time constant, and β is the stretched-exponential exponent which is temperature-dependent.

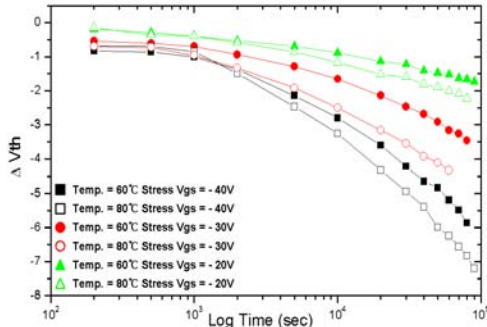
For the ΔV_{min} Fitting, we have drawn out the simple equation from a relationship of ΔV_{th} and ΔV_{min} , as following,

$$\Delta V_{min} = A(stress_V_{gs}) \cdot \Delta V_{th}^{\beta(stress_V_{gs})} \quad (3)$$

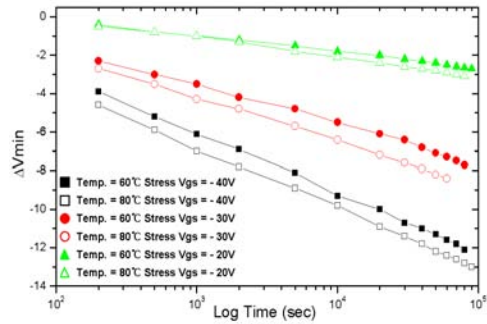
where A and β are fitting parameters which depends on the stress V_{gs} bias. the figure 4 shows measurement values and the fitted curve obtained by eq. (3)

Finally, It is important to estimate the I_{ds} level in the region of sub-threshold. So, we also have fitted the I_{ds} shifted by the stress [10]. As functions of,

$$\Delta I_{ds} = f(Stress\ V_{gs},\ Temperature,\ Stress\ time,\ Measurement\ V_{gs})$$



a) The stress time dependency of ΔV_{th}



b) The stress time dependency ΔV_{min}

Figure 3. (a) The ΔV_{th} and (b) ΔV_{min} as a function of stress time in 60°C (solid symbols) and 80°C (open symbols) BTS condition. The square(\square) symbols stands for the stress $V_{gs} = -40V$, circles(\circ) -30V and triangles(\triangle) -20V, respectively.

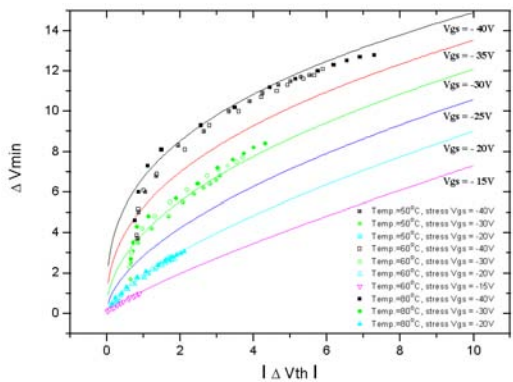


Figure 4. This graph shows the relationships of ΔV_{th} and ΔV_{min} . The calculated curves (lines) and the measurement values (symbols) of ΔV_{min} as a function of ΔV_{th} absolute value. The fitting curves are calculated from eq. (3).

That is,

$$\Delta I_{ds} = A_{Temp} \cdot (\Delta V_{th}(t))^{\beta_{Temp}} \times A_{V_{gs}} \cdot (\Delta V_{th}(t))^{\beta_{V_{gs}}}$$

So,

$$\Delta I_{ds} = A(Temp, Stress_V_{gs}) \times (\Delta V_{th})^{\beta(Temp, Stress_V_{gs})} \tag{4}$$

Where,

$$A(Temp, Stress_V_{gs}) = A_{Temp} \times A_{Stress_V_{gs}}$$

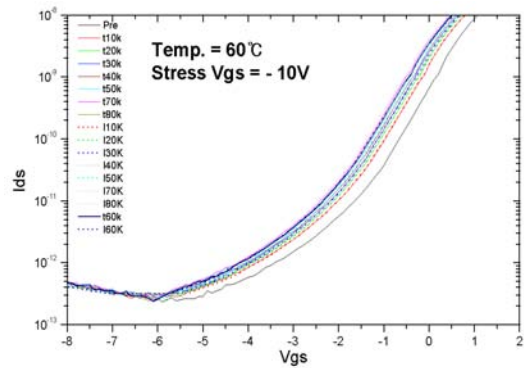
$$\beta(Temp, Stress_V_{gs}) = \beta_{Temp} + \beta_{Stress_V_{gs}}$$

also, from equation 1 and 2, we can plot the ΔV_{th} as the following form,

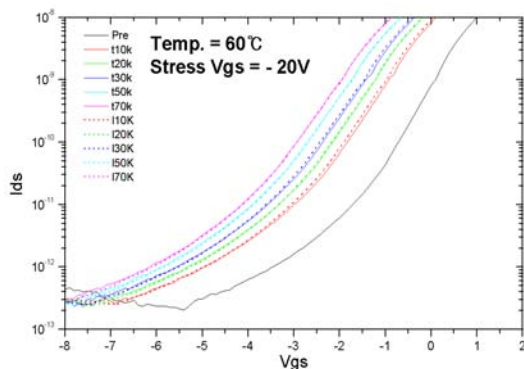
$$\Delta V_{th}(t) = A \cdot t^{\beta} \tag{5}$$

Finally, we can estimate the I_{ds} at any stress time by mixture of the equation (4) and (5).

Figure 5 shows the fitted (dotted lines) and measured (solid lines) I_{ds} - V_{gs} curves at the given stress time and BTS condition. From this curve fitting, we can estimate the I_{ds} level at any using time, any operation voltage, and any operation temperature.



a) stress $V_{gs} = -10V$ and 60°C



b) stress $V_{gs} = -20V$ and 60°C

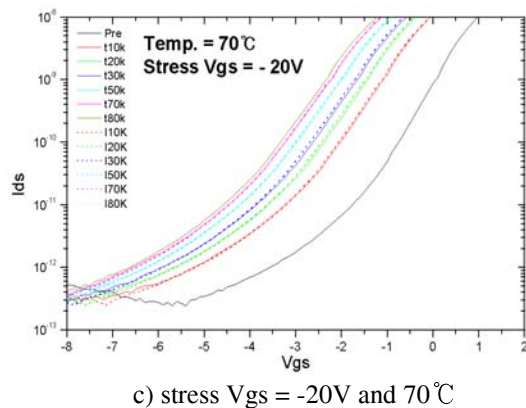


Figure 5. The transfer curves of pre- and post- stressed TFTs with various stress time. The solid lines indicate the measured curves and dotted lines fitted curves with eq (4). Stress time and stress conditions are demonstrated in the plot boxes.

4. Summary

As increasing LCD demands, image quality of worn-out LCD panel as well as the initial LCD is getting important. So a lot of the reliability tests have been done in the LCD industry. However, almost reliability tests are based on the LCD module and need to high cost and long time. Therefore, we have tried to change module based tests to the TFT. Among the faults in reliability tests, especially vertical cross-talk is one of the most frequently revealed faulty in reliability test. Such vertical cross-talk is described that the stress degenerates the transfer characteristics of TFT and shifts up the leakage current level in holding time region after any stress time. So we have investigated electrical instability of TFT in terms of ΔI_{ds} as well as ΔV_{th} . From the ΔI_{ds} fitting curve, we can estimate the leakage current level under operation. It enables us to expect time on the failure caused by the leakage current and to replace the large amount module based reliability test by the TFT based.

5. References

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